POLOS® SPIN150x SPIN COATER

The new POLOS® SPIN150x offers precise, repeatable process control. It is made from natural polypropylene (NPP) or optionally available in chemically resistant PTFE. This new version of the well-proven model comes in a standard and an advanced version. It is ideal for processing a wide range of substrates with a diameter of up to 150 mm or square samples with dimensions 100 x 100 mm.

UNIQUE DESIGN

The unique outer shell and drain design allows easy switching between table-top and in-deck model. The modular design enables the user to upgrade the unit using a wide range of different accessories to ease dispensing and overall handling.

MOTOR HOMING POSITION

The new SPINx-series has the ability to define a motor homing position, allowing for easy integration in robot controlled/automated environments.

EASY CHAMBER ACCESS

The vacuum chuck sits above the edge of the bowl allowing easy access to the wafer/substrate with an end-effector, tweezers or vacuum wand. This is a unique requirement to enable robot handling.

SPECIFICATIONS HARDWARE:

- Liquid filter trap
- Automatic lid, also controllable via foot pedal (advanced version)
- Programmable motor homing position
- Center injection holder for syringe or dispense nozzle
- Lid lock and vacuum sensor for user safety
- Large (detachable) touchscreen display
- USB-port to store recipes on USB-drive and for software updates specifications drive-unit
- Indirect brushless drive unit - up to 12.000 RPM
- High acceleration and accuracy: 1 - 30.000 RPM
- Clockwise/counter clockwise rotation and puddle mode
- Unique design to switch between desktop and in-deck model

AUTO LID

The lid can be automatically opened and closed using the User Interface or alternative a foot pedal (ideal for glovebox usage). In addition, it is also possible to automatically open the lid as a final step of your recipe.

LIQUID FILTER TRAP

The SPINx-series is equipped with a liquid filter trap to protect the spin coater's critical components. It will capture any liquids or resists entering the vacuum lines via the process chamber or vacuum chuck in a liquid container. The container can be viewed through a cut-out in the spinner housing, for easy maintenance.

CONFIGURATION	
Process chamber Material	Natural polypropylene (NPP) or PTFE
Max. substrate diameter	Up to 6" (150 mm) wafers Up to 4" x 4" (100 mm) substrates

SUITABLE FOR:

- Coating
- Cleaning
- Rinse/Dry
- Developing
- Etching
- PDMI and other processes

STANDARD ACCESSORIES:

- Vacuum chuck for 4 - 6-inch wafers
- Fragment adapter for fragments of 10 mm and larger

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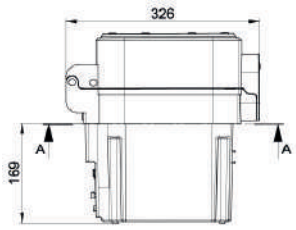
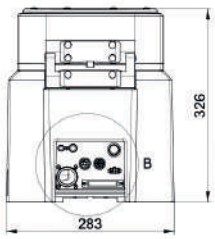
STANDARD VS. ADVANCED VERSION

MODEL	SPIN150x STANDARD	SPIN150x ADVANCED
Liquid filter trap	Yes	Yes
Unique outer shell and drain design	Yes	Yes
Programmable motor home position	Yes	Yes
Center injection holder for syringe or dispense nozzle	Yes	Yes
Lid lock and vacuum sensor for user safety	Yes	Yes
Large (detachable) touchscreen display	Yes	Yes
USB port to store recipes on USB drive	Yes	Yes
Dispense vessel	No	Yes (optional)
Auto-closing lid	No	Yes (optional)
Linear dispense arm	No	Yes (optional)
Backside rinse	No	Yes (optional)
Available in chemical resistant PTFE	No	Yes (optional)

DIMENSIONS SPIN150x





Unique outer/inner shell and drain design allows switch between table-top and in-deck model

OPTIONS

Syringe holder starter kit

Transparant 0,5 mm PET liners

Centering tool

Center dispense system: opus

Corrugated Drainhose

POLOS® Vacuum pump

POLOS® Peristaltic pump

Central dispensing syringe holder

And more. Contact us for all options!

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